

FILE 'KOREAPAT, JICST-EPLUS, JAPIO' ENTERED AT 13:27:27 ON 27 SEP 2006

L1	1959	SEA ABB=ON	PLU=ON	CONTROL### (2A) (SPLITT### OR PRISM OR MIRROR OR REFLECT#)
L2	1559	SEA ABB=ON	PLU=ON	(MIRROR OR REFLECTOR) AND L1
L3	5241	SEA ABB=ON	PLU=ON	(TWO OR DUAL OR SECOND OR ANOTHER OR 2ND) (1W) (MIRROR OR REFLECTOR)
L4	51	SEA ABB=ON	PLU=ON	L3 AND (LITHOG? OR PHOTOLITHOG?)
L5	15	SEA ABB=ON	PLU=ON	L4 AND (WAFER OR SEMICONDUCTOR) D AB 1-15
L6	7	SEA ABB=ON	PLU=ON	L4 AND ALIGN?
L7	5	SEA ABB=ON	PLU=ON	L6 NOT L5 D AB 1-5
L8	10	SEA ABB=ON	PLU=ON	L2 AND (LITHOG? OR PHOTOLITHOG?)
L9	102	SEA ABB=ON	PLU=ON	L2 AND (WAFER OR SEMICONDUCTOR)
L10	1	SEA ABB=ON	PLU=ON	L8 AND ALIGN?
L11	44	SEA ABB=ON	PLU=ON	L2 AND ALIGN?
L12	10	SEA ABB=ON	PLU=ON	L8 OR L10
L13	10	SEA ABB=ON	PLU=ON	L12 NOT (L5 OR L7)

	Ref #	Hits	Search Text
1	S116	35	S115 same (lithography photolithography)
2	S114	44838	CONTROL\$3 near2 (SPLITT\$3 OR PRISM OR MIRROR OR REFLECT\$3)
3	S115	12179	CONTROL\$3 near2 (SPLITT\$3 OR PRISM OR MIRROR OR REFLECT\$3).ab,ti.
4	S117	712	S114 same ((two dual second another) adj mirror)
5	S124	107	S123 and (wafer semiconductor)
6	S123	167	S115 and (lithography photolithography)

	DBs	Time Stamp
1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	2006/09/26 18:22
2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	2006/09/26 18:20
3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	2006/09/26 18:18
4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	2006/09/26 18:21
5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	2006/09/27 10:14
6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	2006/09/26 18:22